

10644954_CLS

Most Frequently Occurring Classifications of Patents Returned
From A Search of 10644954 on July 28, 2004

Original Classifications

9 378/34
6 378/119
5 250/492.2
2 355/67
2 359/366
2 359/857

Cross-Reference Classifications

10 378/34
7 355/67
4 355/53
4 378/119
3 250/492.1
3 250/492.3
3 359/859
3 378/145
3 378/146
3 378/147
3 378/35
3 378/84
3 378/85
2 250/492.2
2 250/504R
2 257/E21.035
2 257/E21.279
2 359/366
2 359/858
2 359/861
2 378/143
2 430/396

Combined Classifications

19 378/34
~~10 378/119~~
9 355/67
7 250/492.2
5 355/53
4 250/492.1
4 359/366
4 359/859
4 378/85
3 250/492.3
3 359/857

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3 359/858
3 378/145
3 378/146
3 378/147
3 378/35
3 378/84
2 250/492.22
2 250/504R
2 257/E21.035
2 257/E21.279
2 355/69
2 356/520
2 359/861
2 378/143
2 430/296
2 430/30
2 430/311
2 430/396

10644954_CLSTITLES

Titles of Most Frequently Occurring Classifications of Patents Returned

From A Search of 10644954 on July 28, 2004

19	378/34	(9 OR, 10 XR)
	Class 378 :	X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
	378/1	SPECIFIC APPLICATION
	378/34	.Lithography
10	378/119	(6 OR, 4 XR)
	Class 378 :	X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
	378/119	SOURCE
9	355/67	(2 OR, 7 XR)
	Class 355 :	PHOTOCOPYING
	355/18	PROJECTION PRINTING AND COPYING CAMERAS
	355/67	.Illumination systems or details
7	250/492.2	(5 OR, 2 XR)
	Class 250 :	RADIANT ENERGY
	250/492.1	IRRADIATION OF OBJECTS OR MATERIAL
	250/492.2	.Irradiation of semiconductor devices
5	355/53	(1 OR, 4 XR)
	Class 355 :	PHOTOCOPYING
	355/18	PROJECTION PRINTING AND COPYING CAMERAS
	355/53	.Step and repeat
4	250/492.1	(1 OR, 3 XR)
	Class 250 :	RADIANT ENERGY
	250/492.1	IRRADIATION OF OBJECTS OR MATERIAL
4	359/366	(2 OR, 2 XR)
	Class 359 :	OPTICS: SYSTEMS
	359/362	COMPOUND LENS SYSTEM
	359/364	.With curved reflective imaging element
	359/365	..Two or more in a series
	359/366	...Concave,convex-combination
4	359/859	(1 OR, 3 XR)
	Class 359 :	OPTICS: SYSTEMS
	359/838	MIRROR
	359/850	.Plural mirrors or reflecting surfaces
	359/857	..With successive reflections
	359/858	...Including curved mirror surfaces in series
	359/859With concave and convex mirrors in series

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- 4 378/85 (1 OR, 3 XR)
 Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
 378/1 SPECIFIC APPLICATION
 378/70 .Diffraction, reflection, or scattering
 analysis
 378/82 ..Spatial energy dispersion
 378/84 ...Monochromator or focusing device
 378/85With plural dispersing elements
- 3 250/492.3 (0 OR, 3 XR)
 Class 250 : RADIANT ENERGY
 250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
 250/492.3 .Ion or electron beam irradiation
- 3 359/857 (2 OR, 1 XR)
 Class 359 : OPTICS: SYSTEMS
 359/838 MIRROR
 359/850 .Plural mirrors or reflecting surfaces
 359/857 ..With successive reflections
- 3 359/858 (1 OR, 2 XR)
 Class 359 : OPTICS: SYSTEMS
 359/838 MIRROR
 359/850 .Plural mirrors or reflecting surfaces
 359/857 ..With successive reflections
 359/858 ...Including curved mirror surfaces in series
- 3 378/145 (0 OR, 3 XR)
 Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
 378/145 BEAM CONTROL
- 3 378/146 (0 OR, 3 XR)
 Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
 378/145 BEAM CONTROL
 378/146 .Scanner
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- 3 378/147 (0 OR, 3 XR)
 Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
 378/145 BEAM CONTROL
 378/147 .Collimator
- 3 378/35 (0 OR, 3 XR)
 Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
 378/1 SPECIFIC APPLICATION
 378/34 .Lithography

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PN junction, depletion barrier or surface barrier, e.g.,
 (EPO) layer, carrier concentration layer

257/E21.085 ...Device having semiconductor body comprising
 mpounds with or without Group IV elements or Group III-V co
 (EPO) impurities, e.g., doping materials

257/E21.211Treatment of semiconductor body using
 iiconductor material on process other than deposition of sem
 f impurity material, or a substrate, diffusion or alloying o
 radiation treatment (EPO)

257/E21.214To change their surface-physical
 ng, polishing, cutting characteristics or shape, e.g., etchi
 (EPO)

257/E21.24To form insulating layer thereon, e.g.,
 hic technique (EPO) for masking or by using photolithograp

257/E21.266Inorganic layer (EPO)

257/E21.271Composed of oxide or glassy oxide or
 oxide based glass (EPO)

257/E21.274Deposition from gas or vapor (EPO)

257/E21.278Deposition of silicon oxide (EPO)

257/E21.279On silicon body (EPO)

2 355/69 (1 OR, 1 XR)
 Class 355 : PHOTOCOPYING
 355/18 PROJECTION PRINTING AND COPYING CAMERAS
 355/67 .Illumination systems or details
 355/69 ..Electricity to lamp controlled

2 356/520 (1 OR, 1 XR)
 Class 356 : OPTICS: MEASURING AND TESTING
 356/450 ~~BY LIGHT INTERFERENCE-(E.G., INTERFEROMETER)~~
 356/520 .Having shearing

2 359/861 (0 OR, 2 XR)
 Class 359 : OPTICS: SYSTEMS
 359/838 MIRROR
 359/850 .Plural mirrors or reflecting surfaces
 359/857 ..With successive reflections
 359/861 ...With three or more successive reflections

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2 378/143 (0 OR, 2 XR)
 Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
 378/119 SOURCE
 378/143 .Target

2 430/296 (1 OR, 1 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
 RADIATION SENSITIVE MATERIAL, OR PRODUCING
 NONPLANAR OR
 PRINTING SURFACE - PROCESS, COMPOSITION, O
 R PRODUCT
 430/296 .Electron beam imaging

2 430/30 (1 OR, 1 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/30 INCLUDING CONTROL FEATURE RESPONSIVE TO A TEST
 OR MEASUREMENT

2 430/311 (1 OR, 1 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
 RADIATION SENSITIVE MATERIAL, OR PRODUCING
 NONPLANAR OR
 PRINTING SURFACE - PROCESS, COMPOSITION, O
 R PRODUCT
 430/311 .Making electrical device

2 430/396 (0 OR, 2 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/396 EFFECTING FRONTAL RADIATION MODIFICATION DURIN
 G
 EXPOSURE, E,G., SCREENING, MASKING, STENCIL
 ING, ETC.
